-null-
D. Thin Film Process Technology 분과

FP1-6  09:30~12:35  Growth of Conductive SrRuOx Films By Combined CVD/ALD Process
저자: Jeong Hwan Han, Woongkyu Lee, Woojin Jeon, and Cheol Seong Hwang
소속: WCU Hybrid Materials Program, Department of Materials Science and Engineering and Inter-university Semiconductor Research Center, Seoul National University

FP1-7  09:30~12:35  Resistive Switching Characteristics in HfO2 Thin Films Depending on the Crystalline Structure
저자: 윤정호, 정형석, 이민환, 김건휘, 송슬지, 석준영, 윤경진, 황철성
소속: 서울대학교 재료공학부 유전박막연구실

FP1-8  09:30~12:35  The Advanced Characteristics of Thermal Silicon Oxide in a Single-Wafer Chamber.
저자: 이웅, 김용석, 신현진, 이우성, 임헌형, 황기현, 신유균
소속: Semiconductor R&D Center, Samsung Electronics Co., Ltd.

FP1-9  09:30~12:35  Development of High Performance and High Stability Transistors without Junctions
저자: 정승민1, 오진웅2, M. Saif Islam2, 조원주1
소속: 1광운대학교, 전자재료공학과, 2Department of Electrical and Computer Engineering, University of California Davis

FP1-10  09:30~12:35  저온 스프레더증착법을 이용한 플렉서블 적층 저장변화 메모리의 제작 및 특성 연구
저자: 한용1, 조경이2, 박석형2, 김상식1,2
소속: 1고려대학교, 나노반도체 공학과, 2고려대학교 전기전자전파 공학과

FP1-11  09:30~12:35  Mn Doped ZnOXS1–X 저장변화 메모리소자 특성에 미치는 전극물질의 영향
저자: 한용1, 조경이2, 윤정권2, 김상식1,2
소속: 1고려대학교 나노반도체 공학과, 2고려대학교 전기전자전파 공학과
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<td>FP1-13</td>
<td>09:30-12:35</td>
<td>Dipole–induced Conduction Process Change in La–incorporated Hafnium–based Dielectric</td>
<td>Tae–Young Jang, Dong–Hyoub Kim, Jungwoo Kim, Jun Suk Chang, Cuong Nguyen Manh, Musarrat Hasan, and Rino Choi</td>
<td>Department of Materials Science and Engineering, Inha University</td>
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<td>FP1-14</td>
<td>09:30-12:35</td>
<td>Impacts of Ar/N2 Flow Rates of Sputtered TiN Metal Gate on Electrical Properties in Gate–First Processed MOS Devices</td>
<td>Dongjun Yoo, Seung–Chan Heo, and Changhwan Choi</td>
<td>Division of Materials Science and Engineering, Hanyang University</td>
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<td>FP1-15</td>
<td>09:30-12:35</td>
<td>Low–Temperature Atomic Layer Deposition of Cobalt Oxide Thin Films Using Cyclopentadienylcobalt Dicarbonyl and Ozone</td>
<td>최규하¹, 한별¹, 박정우², 이원준¹</td>
<td>¹세종대학교 나노신소재공학과, ²한솔케미칼 박막재료팀</td>
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<td>FP1-16</td>
<td>09:30-12:35</td>
<td>Growth of Zn–Sn–O Films using by Plasma Enhanced Atomic Layer Deposition for TFTs Applications</td>
<td>B. K. Lee¹,², D. C. Moon¹, E.-A. Jung¹, S. S. Lee¹, B. K. Park¹, J. H. Hwang², T.-M. Chung¹, C. G. Kim¹, and K. S. An¹</td>
<td>Thin Film Materials Research Team, Korea Research Institute of Chemical Technology, Department of Material Science and Engineering, Hongik University</td>
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<td>FP1-17</td>
<td>09:30-12:35</td>
<td>ZnO Nano–Wire Deposited by Metal Organic Chemical Vapor Deposition (MOCVD) for Anti Reflection Coating (ARC) of Si Solar Cell</td>
<td>최은석¹, 장삼석¹, 임소영², 박성주¹, 김동환¹, 변동진¹</td>
<td>Department of Materials Science and Engineering, Korea University, Department of Nano Semiconductor Engineering, Korea University</td>
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FP1–18 09:30–12:35  Influence of Argon Neutral Particle Beam of High Energy in the Neutral Particle Beam Sputtering System Assisted the Change of Structural Properties on the Amorphous Carbon Film

저자: DongHyek Lee¹, JinNyoung Jang¹, KwangHo Kwon², SukJae You³, BonJu Lee³, and MunPyo Hong¹
소속: ¹Dept. of Display and Semiconductor Physics, Korea University, ²Dept. of Control and Instrumentation Engineering, Korea University, ³National Fusion Research Institute

J. Nano-Science & Technology 분과

FP1–19 09:30–12:35  Fabrication of Silicon Nanowire Based Thermoelectric Device and Temperature Sensor Calibration

저자: Wonchul Choi¹,2, Youngsam Park¹, Younghoon Hyun¹, Taehyoung Zyung¹, Jaehyun. Kim¹,3, Mincheol Shin², and Moongyu Jang¹,3
소속: ¹Convergence Components & Material Research Lab., ETRI, ²Department of Electrical Engineering, KAIST, ³Department of Advanced Device Technology, UST

FP1–20 09:30–12:35  Fabrication of Sub–30nm Pillar Array by Oxygen Plasma Treatment

저자: Bongho Kim¹, Daehong Kim¹, Jihun Kwon¹, Sungwoo Chun¹, Seonjun Choi¹, and Seung–Beck Lee¹,2,3
소속: ¹Department of Electronic Engineering, Hanyang University, ²Department of Nanoscale Semiconductor Engineering, Hanyang University, ³Institute of Nano Science and Technology, Hanyang University

FP1–21 09:30–12:35  Thin Film Fabrication and Simultaneous Reduction of Deposited Graphene Oxide Platelets by Electrophoretic Deposition

저자: Sung Jun An¹
소속: ¹School of Advanced Materials and Systems Engineering, Kumog National Institute of Technology

FP1–22 09:30–12:35  Ion–gel Gate Dielectrics for Arrayed Si Nanowires Field Effect Transistors

저자: 최진용, 조경아, 김상식
소속: 고려대학교 전기전자전파공학과
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<td>FP1–24</td>
<td>09:30–12:35</td>
<td>Graphene Sheets as p–type Transparent Conducting Electrodes in GaN Light Emitting Diodes</td>
<td>Jung Min Lee, Hae Yong Jeong, and Won Il Park</td>
<td>Division of Materials Science and Engineering, Hanyang University</td>
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<td>FP1–26</td>
<td>09:30–12:35</td>
<td>N–type Carbon Nanotube Network Device based on Tunneling through SnO2</td>
<td>Young Jun Heo, Jun Ho Cheon, Seok Ha Lee, Jaeheung Lim, and Young June Park</td>
<td>School of Electrical Engineering, Seoul National University</td>
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<td>FP1–27</td>
<td>09:30–12:35</td>
<td>The Predicted Crystal Structure of Li4C6O6, an Organic Cathode Material for Li–ion Batteries: First–principles Multi–scale Computational Study</td>
<td>Dong–Hwa Seo¹, Hyungjun Kim², Haegyeom Kim¹, William A. Goddard III²,³, and Kisuk Kang¹</td>
<td>¹Department of Materials Science and Engineering, Seoul National University, ²Graduate School of EEWS, KAIST, ³Materials and Process Simulation Center, California Institute of Technology</td>
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<td>FP1–28</td>
<td>09:30–12:35</td>
<td>Fabricated Various Metallic Nano–sized Pattern using Ag Ink Printing Technique</td>
<td>오상철¹, 신주현², 김진승², 김양두³, 이현¹,²,³</td>
<td>¹고려대학교 나노반도체공학과, ²고려대학교 신소재공학과, ³고려대학교 바이오–마이크로 시스템 협동과정</td>
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FP1–29 09:30–12:35 A Graphene/Nanocluster Hybrid Nanomaterial-Based Gas Sensor
저자: I.-S. Kang and C. W. Ahn
소속: National Nanofab Center

FP1–30 09:30–12:35 Color Tunable OLEDs using Localized Surface Plasmons
저자: Illhwan Lee, Kihyon Hong, Sungjun Kim, and Jong–Lam Lee
소속: Department of Materials Science and Engineering and Division of Advanced Materials Science, POSTECH

FP1–31 09:30–12:35 Analytic Model of Spin–Torque Oscillators(STO) for Circuit–Level Simulation
저자: 안소라1, 임혜인1, 서수만2, 이경진2, 신형순1, 이승준1
소속: 1이화여자대학교 전자공학과, 2고려대학교 신소재공학과

FP1–32 09:30–12:35 Porosity Modulated Silicon Nanowires
저자: Jungkil Kim1,2 and Woo Lee1,2
소속: 1Korea Research Institute of Standards and Science, 2Department of Nano Science, University of Science and Technology

N. VLSI CAD 분과

FP1–33 09:30–12:35 Thermal Modeling of 3D Stacked MLC NAND Flash Memory
저자: 김동기1, 유승주1, 이승구1
소속: 1포항공과대학교 전자전기공학과

FP1–34 09:30–12:35 System Model for CPU/GPU Architecture
저자: 이성광1, 유승주1, 정재웅2, 윤동혁2, 김대현2
소속: 1포항공과대학교 전자전기공학과, 2Intel Corporation

FP1–35 09:30–12:35 High–Throughput Double–Binary MAP Decoder with Reduced Memory Requirement
저자: 김지훈
소속: 충남대학교 전자공학과
FP1–36 09:30–12:35 Promoting Data Reuse on Shared Memory of Hybrid System
저자: Toan X. Mai, Yeonghun Jeong, Jongeun Lee
소속: School of Electrical and Computer Engineering, Ulsan National Institute of Science and Technology

FP1–37 09:30–12:35 쓰기 데이터 특성 파악을 통한 Wear-Leveling
저자: 윤태희, 박상훈, 서혁준, 정의영
소속: 연세대학교, 전기전자공학과

FP1–38 09:30–12:35 Interleaved Garbage Collection Scheme using Dynamic Channel/Way Allocation for Solid-State Drive
저자: 김동건, 박상훈 서혁준, 정의영
소속: 연세대학교, 전기전자공학부

Q. Metrology, Inspection, and Yield Enhancement 분과

FP1–39 09:30–12:35 초음속 나노입자빔을 이용한 실리콘 웨이퍼 표면오염입자(10nm) 제거 실험
저자: 김인호, 이진원
소속: 포항공과대학교 기계공학과

FP1–40 09:30–12:35 Characterization of Overlay Error Induced by Film Stress Using Local Stress Monitoring Tool
저자: C. H. Lee¹, J. T. Kim¹, J. H. Kim¹, H. Y. Yoo¹, I. K. Han¹, and W. S. Yoo²
소속: ¹Hynix Semiconductor Inc., ²WaferMasters, Inc.

FP1–41 09:30–12:35 The Pattern Wiggling CD Metrology Using Flexible Scan & Dense Function
저자: 김종태¹, 이창환¹, 유형원¹, 한일근¹, 고흥보², 곽동수³
소속: ¹하이닉스 반도체 MI팀, ²하이닉스 반도체 DRAM공정AP팀, ³Hitachi High-Technologies

FP1–42 09:30–12:35 Electron Beam Inspection of Cell Mat Edge Using Image Averaging and Comparison Method
저자: G. Kwon¹, J. H. Oh¹, D. Y. Mun¹, H. W. Yoo¹, J. C. Jo², J. S. Koo², M. Nozoe², T. Ninomiya², T. Hiroi², and H. Okuda²
FP1–43  09:30–12:35  The Measurement of OCD (Optical critical dimension) for Yield Enhancement at Edge Die
저자: Seok Park, Won Sik Yun, Chang Hwan Lee, Sung Su Kim, Hyung Won Yoo, and Il Keoun Han
소속: Hynix Semiconductor Inc.

FP1–44  09:30–12:35  The MASK CD Control (CDC) Using OCD Applications
저자: Hyun Chul Shin, Seok Park, Won Sik Yun, Chang Hwan Lee, Hyung Won Yoo, and Il Keoun Han
소속: Hynix Semiconductor Inc.

FP1–45  09:30–12:35  The In-Line Monitoring Method of ZAZ Thickness Using WD–XRF
저자: Jun Soo Kim, Sang Hoon Son, Shin Wang Ju, Hyung Won Yoo, and Il Keoun Han
소속: Hynix Semiconductor Inc.

저자: Y. J. Park1 and D. R. Lee2
소속: 1Pohang Accelerator Laboratory, Pohang University of Science and Technology, 2Department of Physics, Soongsil University

FP1–47  09:30–12:35  Improvement of Measurement Resolution for Determining Geometrical Thickness of a Silicon Wafer using a Femtosecond Pulse Laser
저자: 맹새롬1,3, 박정재1, 진종현1,2, 김재현1,2, 강주식1,2, 김종안1, 오성럼3
소속: 1한국표준과학연구원 길이센터, 2과학기술연합대학원대학교, 3충남대학교 물리학과

FP1–48  09:30–12:35  다결정성텅스텐 나노팁의 저전압 전계방출 안정성 평가
저자: 정재웅, 안상정, 박창준, 김주현, 송문, 김달현, 배문섭, 이학주, 조양구
소속: 한국표준과학연구원 나노이미징기술센터